

Abstract

The present invention discloses a film deposition apparatus, a vaporization detection device and a vaporization detection method. The film deposition apparatus, comprising: a vaporizer, configured to vaporize a liquid reactant to form a reaction gas; a reaction chamber, connected to the vaporizer via a pipeline, and configured to obtain the reaction gas from the vaporizer to perform film deposition; and a vaporization detection device, disposed between the vaporizer and the reaction chamber, and configured to detect a vaporization degree of the liquid reactant to permit or prevent a vaporized liquid reactant from entering the reaction chamber. By using the film deposition apparatus, the vaporization rate of the reaction gas to be introduced into the reaction chamber can be effectively detected, thereby avoiding a series of problems such as particle contamination and non-uniform deposition of films during the deposition process caused by incomplete vaporization of the reaction gas.

(FIG. 3)